

AME P5000 Chamber C



Facts

The AME P5000 is a multi-chamber tool set up for a variety of processes

- Chamber C - RIE of Silicon Dioxide
 - CHF₃, CF₄, and O₂ are used to reactively ion etch silicon dioxide.
- Other Chambers
 - AME P5000 Chamber A - PECVD of TEOS Silicon Dioxide
 - AME P5000 Chamber B - PECVD of Silicon Nitride / Amorphous Silicon

Personnel

- Tool Engineer - John Nash
- Process Engineer - Sean O'Brien
- Process Engineer - Patricia Meller

Manuals & Users

- P5000 Manual
- P5000 Certification Checklist